

Notice of Allowability

Application No.

10/596,422

Applicant(s)

PONOMAREV, YOURI

Examiner

DANIEL WHALEN

Art Unit

2829

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to 06/12/2008.
2. ☒ The allowed claim(s) is/are 1,2,4, and 6-8.
3. ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some* c) ☐ None of the:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. ____.
3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).
- * Certified copies not received: ____.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.

THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
5. ☐ CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
- (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
- 1) ☐ hereto or 2) ☐ to Paper No./Mail Date ____.
- (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date ____.
- Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).**
6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

- | | |
|--|--|
| 1. <input type="checkbox"/> Notice of References Cited (PTO-892) | 5. <input type="checkbox"/> Notice of Informal Patent Application |
| 2. <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 6. <input checked="" type="checkbox"/> Interview Summary (PTO-413),
Paper No./Mail Date <u>07/07/2008</u> . |
| 3. <input type="checkbox"/> Information Disclosure Statements (PTO/SB/08),
Paper No./Mail Date ____ | 7. <input checked="" type="checkbox"/> Examiner's Amendment/Comment |
| 4. <input type="checkbox"/> Examiner's Comment Regarding Requirement for Deposit
of Biological Material | 8. <input checked="" type="checkbox"/> Examiner's Statement of Reasons for Allowance |
| | 9. <input type="checkbox"/> Other ____. |

DETAILED ACTION

Drawings

1. The drawings were received on 01/28/2008 regarding fig. 1-5. These drawings are accepted.

Allowable Subject Matter

2. **Claims 1, 2, 4, and 6-8** are allowed.

Reasons for Allowance

3. The following is an examiner's statement of reasons for allowance:

Regarding Claim 1, the prior art of record, alone or in combination, and to the examiner's knowledge does not teach, disclose, suggest, or render obvious, at least to the skilled artisan, the instant invention regarding a method of making a strained Si layer, particularly characterized by the steps of fabricating the device in combination with a step of depositing a silicon dioxide capping layer on said remaining monocrystalline SiGe layer; and bonding the silicon dioxide capping layer to a silicon dioxide surface layer of a second substrate and thereafter removing said support layer and said buried silicon dioxide layer by etching. Claims 2, 4, and 6-8, which depend from an independent claim 1, is allowed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably

accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

EXAMINER'S AMENDMENT

4. In Claim 1, line 2, delete "formation of an epitaxial SiGe layer" and insert -- forming an epitaxial SiGe layer--

In Claim 1, line 4, delete "residing on the buried silicon dioxide layer," and insert --residing on the buried silicon dioxide layer;--

In Claim 1, line 5, delete "ion implantation of said Si surface layer" and insert --ion implanting said Si surface layer--

In Claim 1, line 8, delete "remaining monocrystalline SiGe layer," and insert --remaining monocrystalline SiGe layer;--

In Claim 1, line 10, delete "forming a layer stack on said buried silicon dioxide layer," and insert --forming a layer stack on said buried silicon dioxide layer;--

In Claim 1, line 12, delete "a silicon dioxide capping layer on said remaining monocrystalline SiGe layer," and insert --a silicon dioxide capping layer on said remaining monocrystalline SiGe layer;--

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to DANIEL WHALEN whose telephone number is (571)270-3418. The examiner can normally be reached on Monday-Friday, 7:30am to 5:00pm, EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Ha Nguyen can be reached on (571) 272-1678. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/D. W./
Examiner, Art Unit 2829
07/08/2008

Daniel Whalen

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/Ha T. Nguyen/

Supervisory Patent Examiner, Art Unit 2829